

Number	Hits	Search Text	DB	Time
	26046	chemical adj mechanical adj polishing	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/1
	19881	chemical adj mechanical adj polishing	USPAT; US-PGPUB	2003/10/28 16:
	5016	(chemical adj mechanical adj polishing).clm.	USPAT;	2003/10/27 11:50
	872	(216/52) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27 11:30
	380	(216/88) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27 11:3
	334	(216/89) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27 11:
	370	(216/93) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27 11
	1637	(438/692) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27 11
	6	((("6383332") or ("6419785") or ("6361647")) .PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27 1
	258	(156/345.12) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27
	78	(156/345.13) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/27
	44	(156/345.14) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/2
	357	(216/38) .CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/
	675	((chemical adj mechanical adj polishing) and control\$5) .clm.	USPAT; US-PGPUB	2003/10
	160	((chemical adj mechanical adj polishing) and (endpoint near3 detect\$3).clm.	USPAT; US-PGPUB	2003/10
	31	((chemical adj mechanical adj polishing) and program\$1) .clm.	USPAT; US-PGPUB	2003/10
	82	((chemical adj mechanical adj polishing).clm.) and (endpoint near3 detect\$3).clm.	USPAT; US-PGPUB	2003/10

	634	(438/693).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/27 11:53
	83	(chemical adj mechanical adj polishing) and ((particle adj size) near3 measur\$5)	USPAT;	2003/10/28 16:05
	1945	(chemical adj mechanical adj polishing) and (controller)	US-PGPUB	2003/10/27 13:39
	245	(chemical adj mechanical adj polishing) and controller and laser and distribution	USPAT;	2003/10/27 13:39
	78	(chemical adj mechanical adj polishing) and ((particle adj size) and controller and slurry)	US-PGPUB	2003/10/27 14:15
	227	((chemical adj mechanical) or chemical-mechanical) adj (polishing or planarizing)) and (particle adj size adj distribution)	USPAT; US-PGPUB	2003/10/27 14:18
	78	(156/345.13).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 09:53
	73	((156/345.13).CCLS.) and (polish\$3 or planariz\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 09:54
	45	((156/345.13).CCLS.) and (polish\$3 or planariz\$5) and (speed or velocity)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 15:59
	7	(("6562185") or ("6464824") or ("6261851")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 10:15
	6	((("5710069") or ("6383332") or ("5846398"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 10:18
	4	((("5865665") or ("5562530"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 13:37
	2	("6117779").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 13:38
	1	2001-121950.NRAN.	DERWENT	2003/10/28 13:52
	91	(chemical adj mechanical adj polishing) and controller and (constant near3 speed)	USPAT;	2003/10/28 15:27
	13	(chemical adj mechanical adj polishing) and controller and (constant near3 removal)	US-PGPUB	2003/10/28 15:08
	2	("5791970").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/10/28 15:27
	1	1998-455870.NRAN.	DERWENT	2003/10/28 15:27
	1	"3028711".PN.	USPAT	2003/10/28 15:27
	1	"5664990".PN.	USPAT	2003/10/28 15:28
	1	"5658185".PN.	USPAT	2003/10/28 15:28
	23	5791970.URPN.	USPAT	2003/10/28 15:28
	6	("3028711" "3162986" "3500591" "4059929" "5658185" "5664990").PN.	USPAT	2003/10/28 15:57
			USPAT	2003/10/28 15:58

	72	((156/345.13).CCLS.) and (polish\$3 or planariz\$5) and (speed or velocity or time)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/28 16:00
	36	((156/345.13).CCLS.) and (polish\$3 or planariz\$5) and controller	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/28 16:00
	86	(chemical adj mechanical adj polishing) and ((particle adj size) near3 (measur\$5 or sensor))	USPAT; US-PGPUB	2003/10/28 16:07
	112	(chemical adj mechanical adj polishing) and (particle adj size) and controller	USPAT; US-PGPUB	2003/10/28 16:08
	150	(chemical adj mechanical adj polishing) and (particle\$1 near2 size) and controller	USPAT; US-PGPUB	2003/10/28 16:08
	695	((chemical adj mechanical adj (planarizing or polishing)) and control\$5) .clm.	USPAT; US-PGPUB	2003/10/28 16:19
	284	((chemical adj mechanical adj (planarizing or polishing)) and control\$5) .clm.) and (rate near2 (polishing or removal))	USPAT; US-PGPUB	2003/10/28 16:20
	5099	(chemical adj mechanical adj (planarizing or polishing)).clm.	USPAT; US-PGPUB	2003/10/28 16:20
	124	((chemical adj mechanical adj (planarizing or polishing)).clm.) and (constant with (rate near2 (polishing or removal)))	USPAT; US-PGPUB	2003/10/28 16:20
	2	("6251901").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/29 12:38
	12	(("6117779") or ("5865665") or ("5759918") or ("5710069") or ("5846398") or ("6077437")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/29 12:58